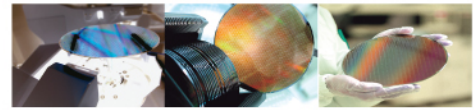


The Development and the commercialization of the Mask Aligner for wafer
Midas System will continue to grow along with the value creation for our customers.



www.aligner.co.kr / www.midas-system.com

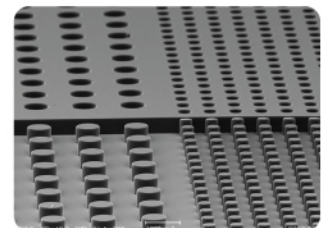
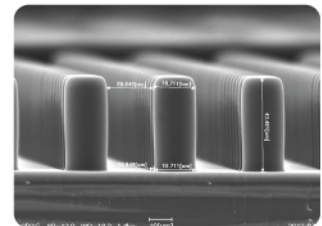
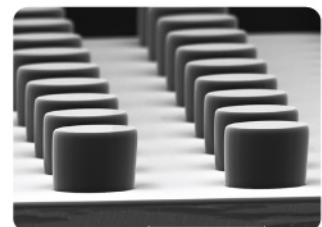
✚ MDA-80MS



The MDA-80MS offers a higher alignment accuracy and more flexible process of all applications. This is good for piece to 8inch process for research and reliable. This stabilized system will give you a reduction of experimental hours at all times.



▼ SEM Image



ITEM	SPECIFICATIONS
Substrate Size	Up to 8 inch (200 × 200mm)
UV Lamp Power	1kW
Resolution	1 μ m with 1 μ m thin PR @ Si wafer
Alignment Accuracy	< 1.0 μ m
Lamp Uniformity	≤ 5%
Uniform Beam Size	9.25" × 9.25"
365nm Beam Intensity	> Max 30mW/cm ²
Process mode	Vacuum, Hard, Soft and Proximity
Dimension	1,400(W) × 1,100(D) × 1,600(H)
Option	BSA / Nanoimprint / Bond aligner kit



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